

SUBJECT CODE : 24-509-0105

SUBJECT NAME : DIGITAL INTEGRATED CIRCUITS LAB

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MOSFET CHARACTERISTICS

MOSFET is a very popular kind of IG-FET. The full form of MOSFET is the Metal Oxide Semiconductor Field Effect Transistor. It is a three-terminal device that uses the electric field to regulate and maintain the flow of current. The three terminals are Gate, Drain, and Source

LONG CHANNEL n-MOSFET

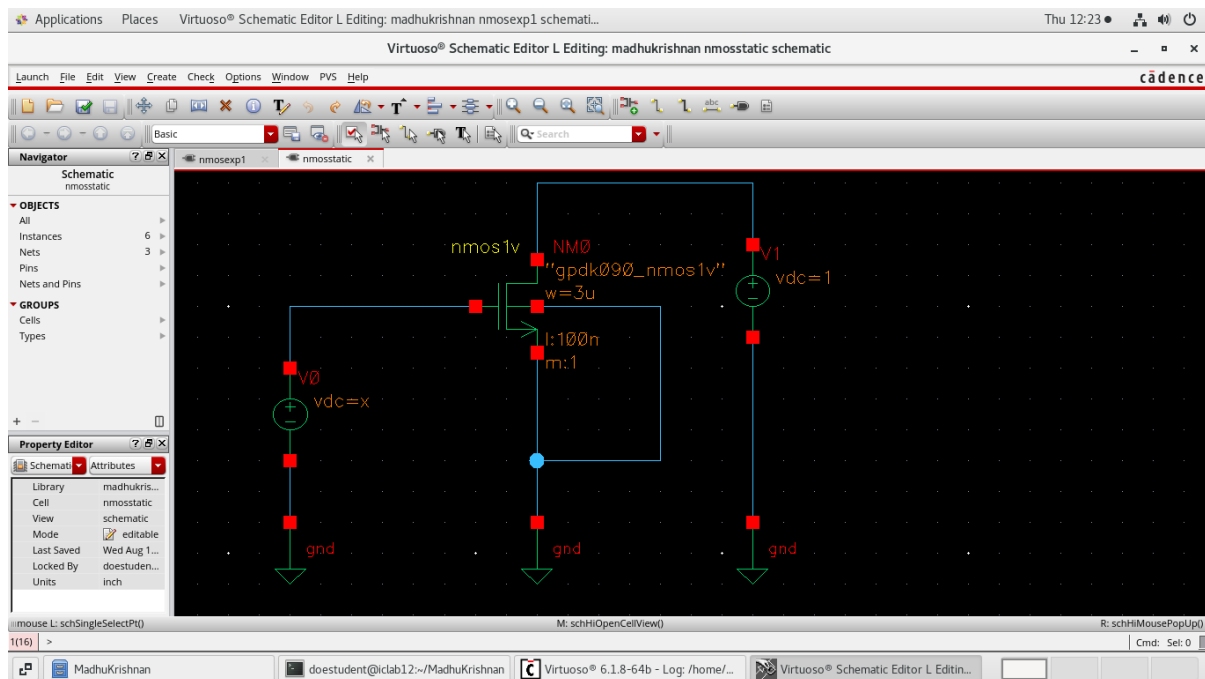
A long channel n-MOSFET with following dimensions were placed in Cadence Virtuoso.

Length, $L = 1 + (\text{Roll Number}/5) = 1 + (10/5) = 3\mu\text{m}$

Width, $W = 1 + (\text{Roll Number}/5) = 1 + (10/5) = 3\mu\text{m}$

Technology : 90 nm Technology

$V_{DD} = 1\text{V}$ is connected to the MOSFET.

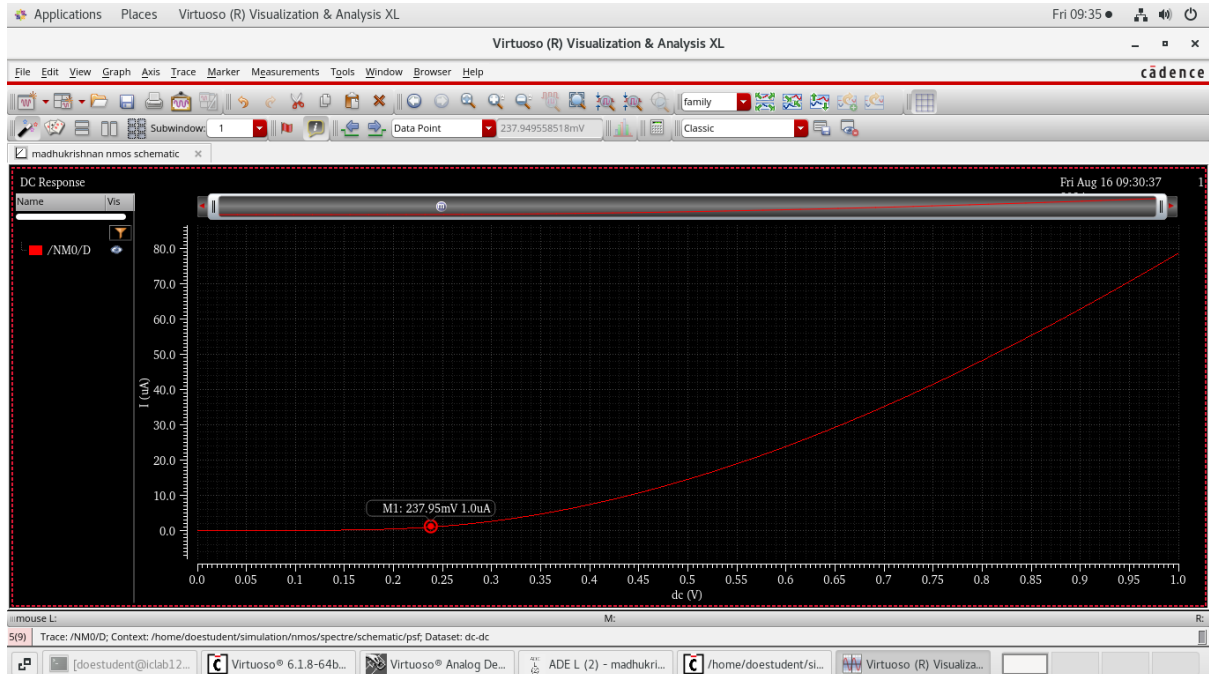


Schematic diagram

For this specific MOSFET, $(W/L) = 1$.

THRESHOLD VOLTAGE V_{T0}

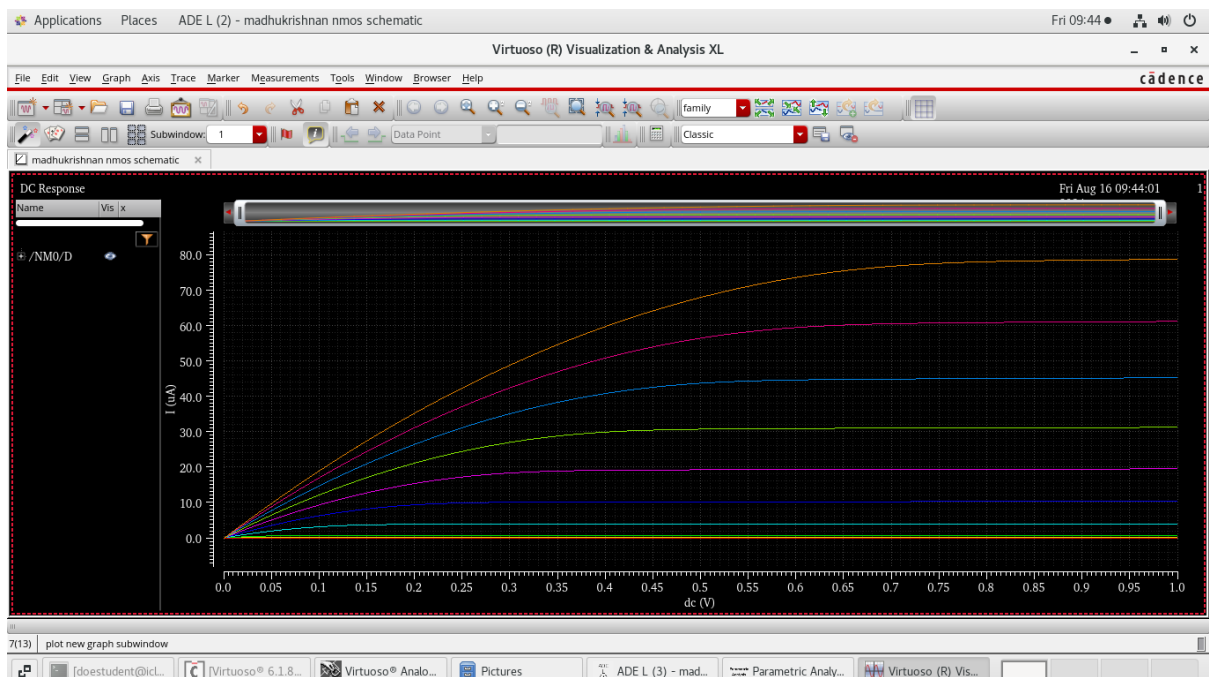
V_{SB} is kept at 0V. The threshold voltage V_{T0} is found using DC analysis. V_{GS} is raised from 0 to 1V. The V_{GS} of corresponding point in DC analysis graph at which the I_{DS} turn from nanoampere range to microampere range is noted as V_{T0}



I_{DS} vs V_{DS} for $V_{GS} = 1V$

$$V_{T0} = 238 \times 10^{-3} V$$

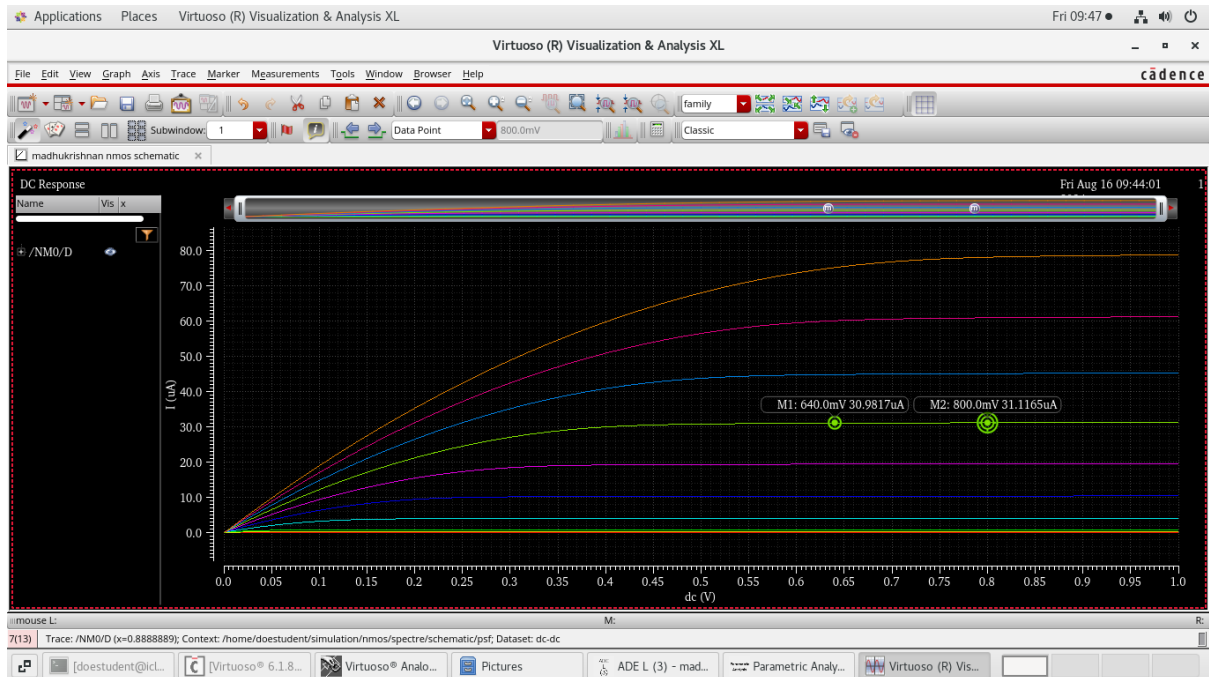
The I_D vs V_{DS} graph is plotted using DC analysis for varying V_{GS} and the following graph is obtained.



I_D vs V_{DS} for varying V_{GS}

EXTRACTION OF PARAMETERS

V_{T0} is found from the graph. The following calculations are done to calculate $\mu_n C_{ox}$ and λ .



2 Points are taken in saturation region with same V_{GS}

$$I_{DS} = \mu_n C_{ox} (W/2L) (V_{GS} - V_T)^2 (1 + \lambda V_{DS}) \quad [1]$$

For M1

$$I_{DS} = 30.9817 \times 10^{-6} \text{ A}$$

$$W/L = 1$$

$$V_{GS} = 666.7 \times 10^{-3} \text{ V}$$

For M2

$$I_{DS} = 31.1165 \times 10^{-6} \text{ A}$$

$$W/L = 1$$

$$V_{GS} = 666.7 \times 10^{-3} \text{ V}$$

Substituting the above values in [1], we get

$$\lambda = 0.0296751 \text{ V}^{-1}$$

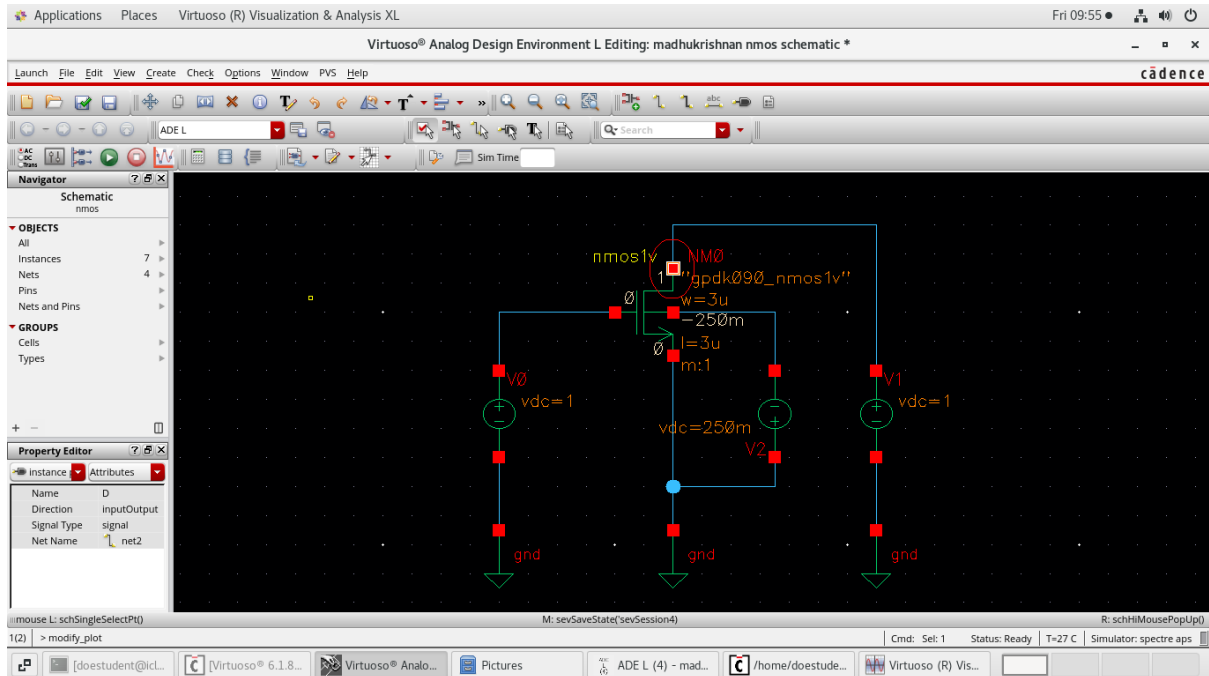
Substituting the value of λ and M1 in [1], we get $\mu_n C_{ox}$.

$$\mu_n C_{ox} = 331.2862 \text{ } \mu\text{A/V}^2$$

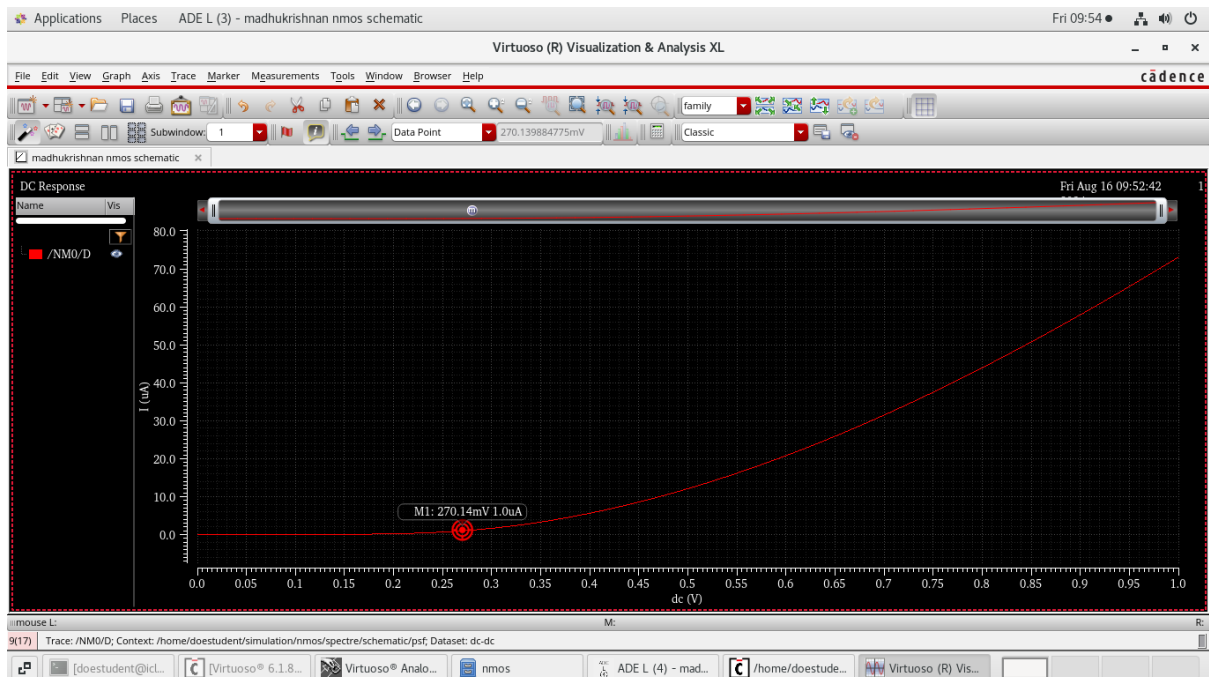
EXTRACTION OF PARAMETERS WITH $V_{SB} \neq 0$

V_{SB} is introduced between source and body. The corresponding DC analysis results are as following.

$$V_{SB} = 0.250 \text{ V}$$



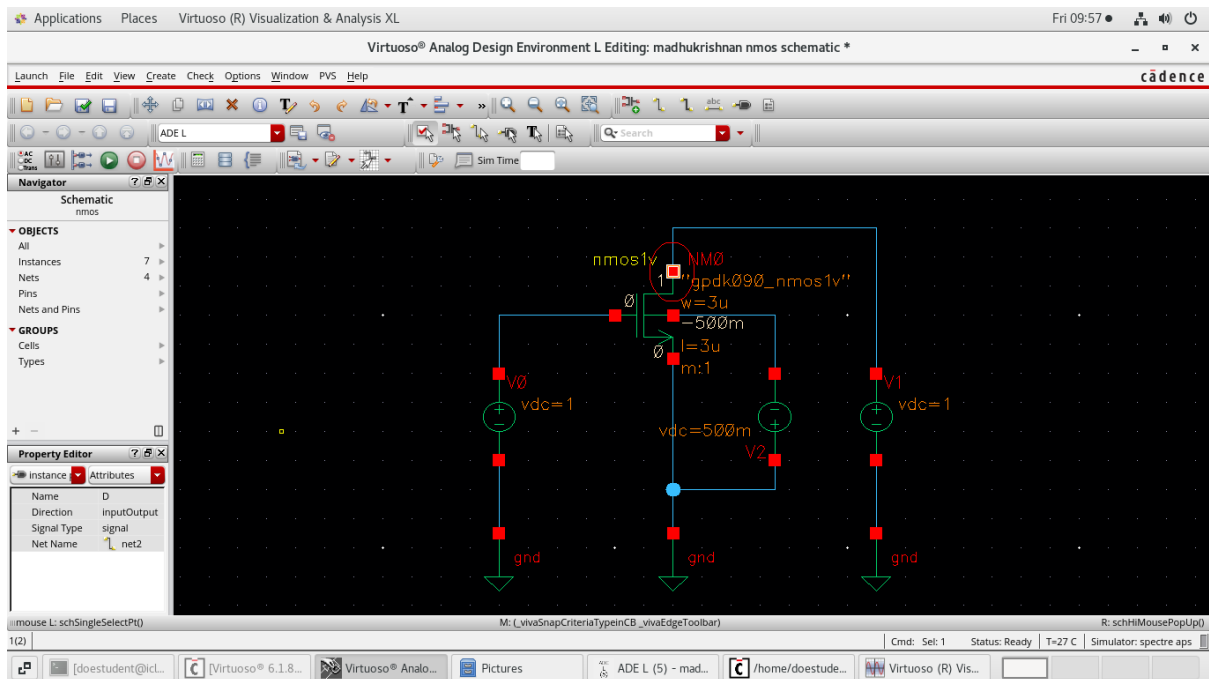
Schematic diagram for NMOS with $V_{SB} = 0.250 \text{ V}$



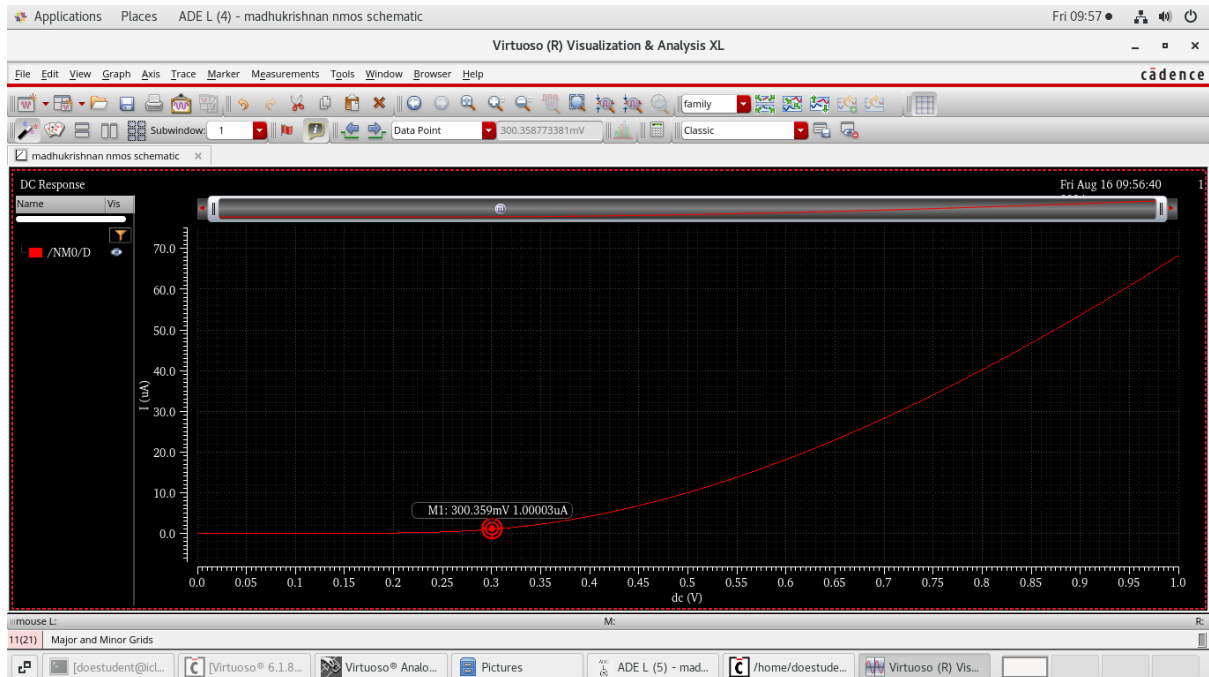
DC Analysis Graph for $V_{SB} = 0.250 \text{ V}$

Threshold voltage, $V_T = 271 \text{ mV}$

$$V_{SB} = 0.500 \text{ V}$$



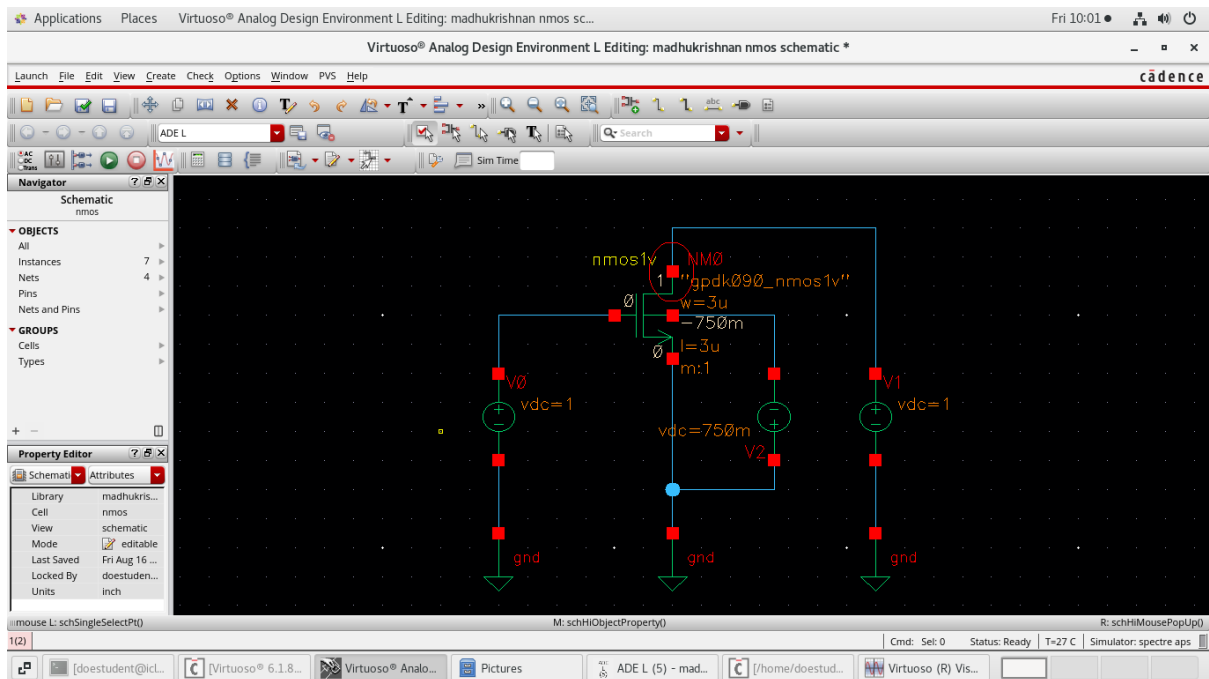
Schematic diagram for NMOS with $V_{SB} = 0.500 \text{ V}$



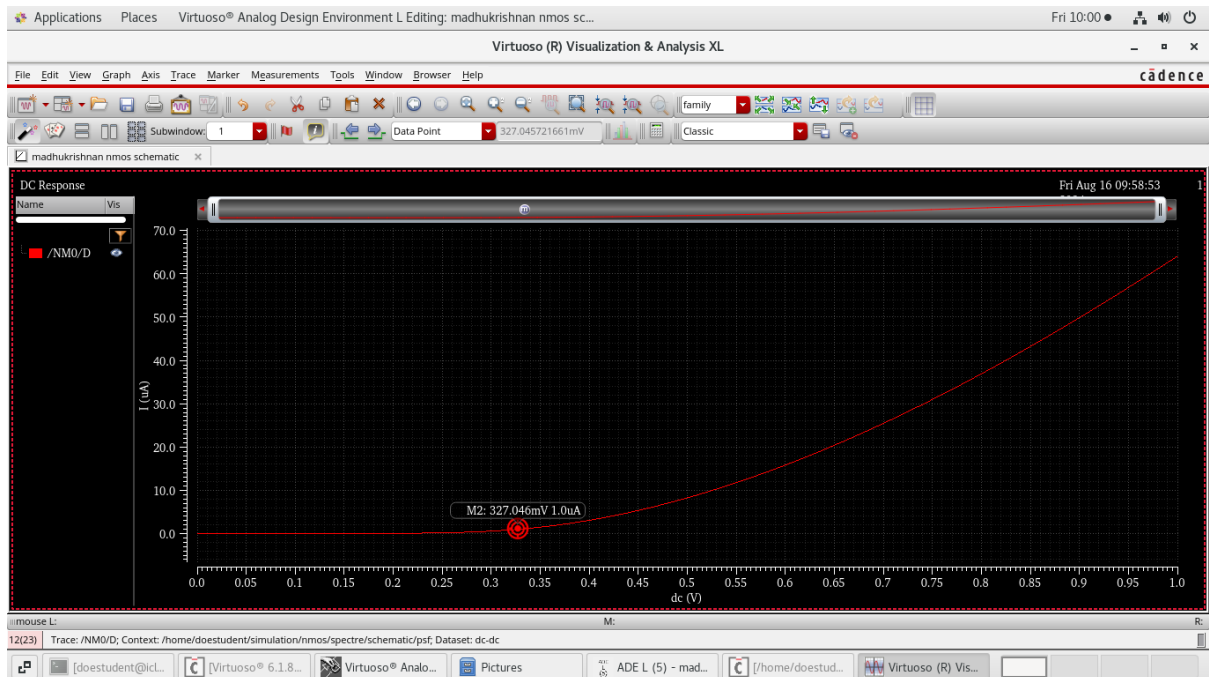
DC Analysis Graph for $V_{SB} = 0.500 \text{ V}$

Threshold voltage, $V_T = 301 \text{ mV}$

$$V_{SB} = 0.750 \text{ V}$$



Schematic diagram for NMOS with $V_{SB} = 0.750 \text{ V}$



DC Analysis Graph for $V_{SB} = 0.750 \text{ V}$

$$\text{Threshold voltage, } V_T = 328 \text{ mV}$$

The results are tabulated as following

V_{SB}	V_T
0 V	238 mV
250 mV	271 mV
500 mV	301 mV
750 mV	328 mV

We know,

$$V_{TH} = V_{T0} + \gamma \sqrt{(-2\phi_F + V_{SB})} - \sqrt{(-2\phi_F)}$$

V_{TH} = Threshold Voltage

V_{T0} = Threshold voltage for $V_{SB} = 0V$

ϕ_F = Fermi potential for substrate

γ = Body effect coefficient

When V_{SB} is increased $|-2\phi_F + V_{SB}|$ is increased and $\gamma \sqrt{(-2\phi_F + V_{SB})} - \sqrt{(-2\phi_F)}$ is increased. This makes V_{T0} to increase. We can say that the body effect comes into action when V_{SB} is provided. The V_{SB} opposes the gate voltage. The gate must be provided a higher voltage than V_{T0} so that the MOSFET goes past the cutoff region and turns on. This body effect can be observed in both short channel and long channel MOSFETs.

SHORT CHANNEL n-MOSFET

A short channel n-MOSFET with following dimensions is placed in cellview.

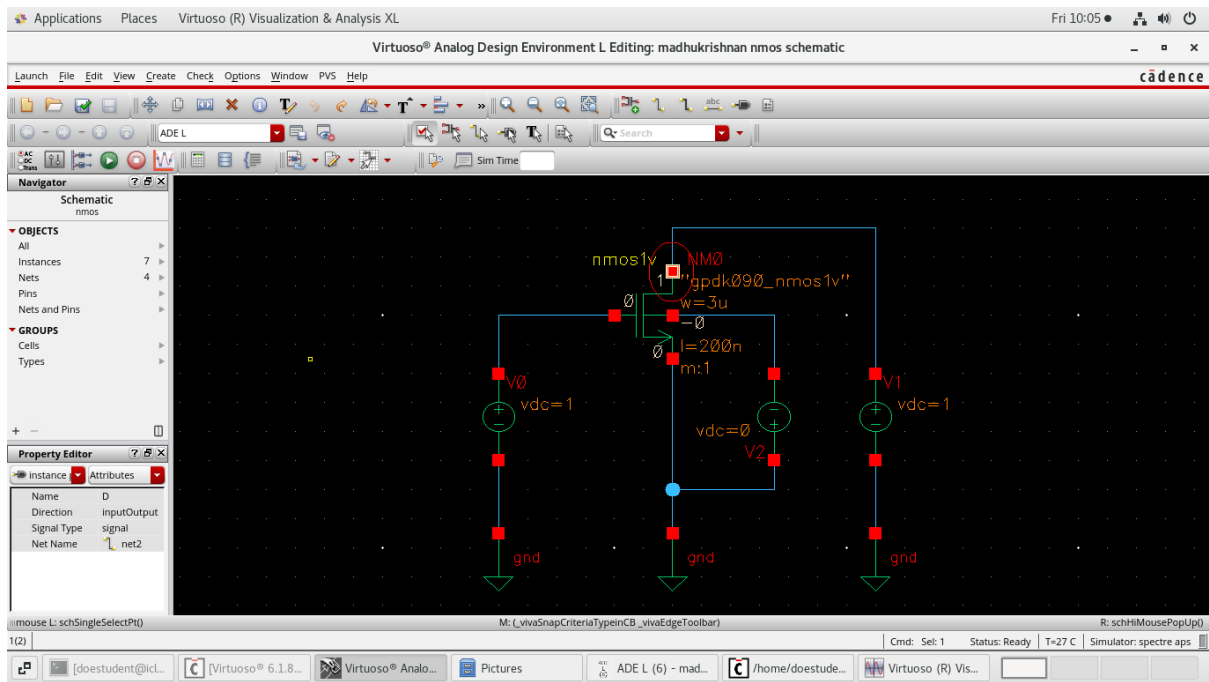
Length, 200 nm

Width, $W = 1 + (\text{Roll Number}/5) = 1 + (10/5) = 3\mu\text{m}$

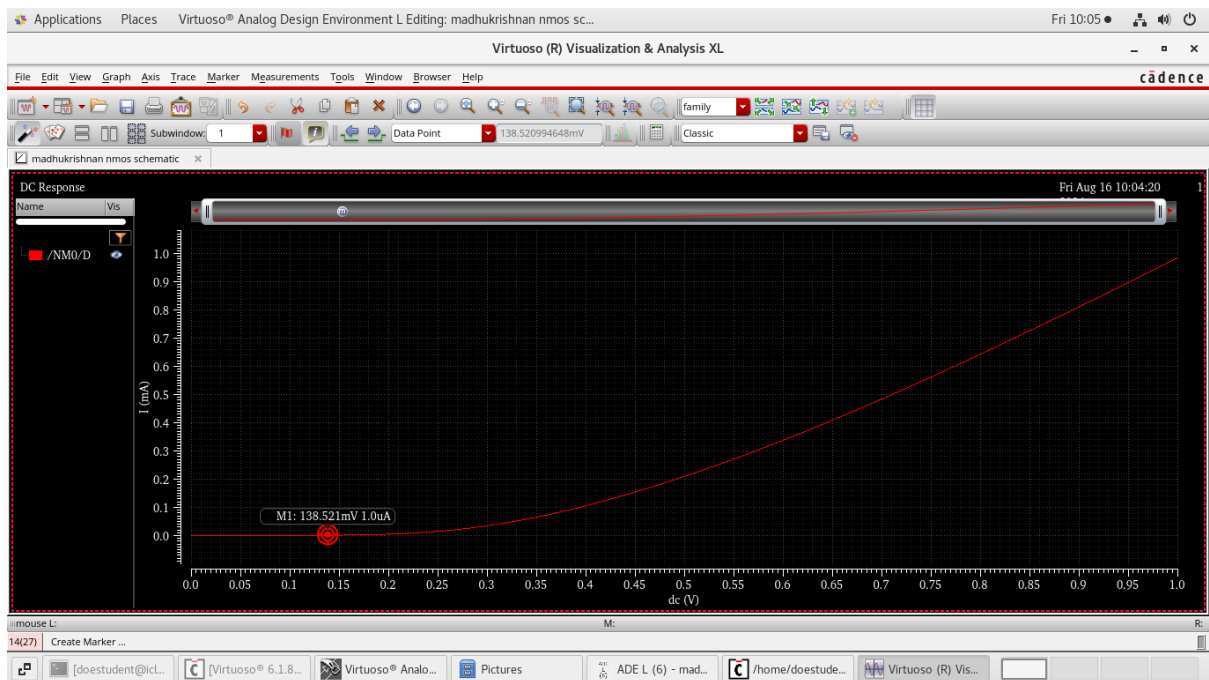
$W/L = 15$

$V_{DD} = 1\text{ V}$ is connected to the MOSFET.

$V_{SB} = 0\text{ V}$



Schematic diagram

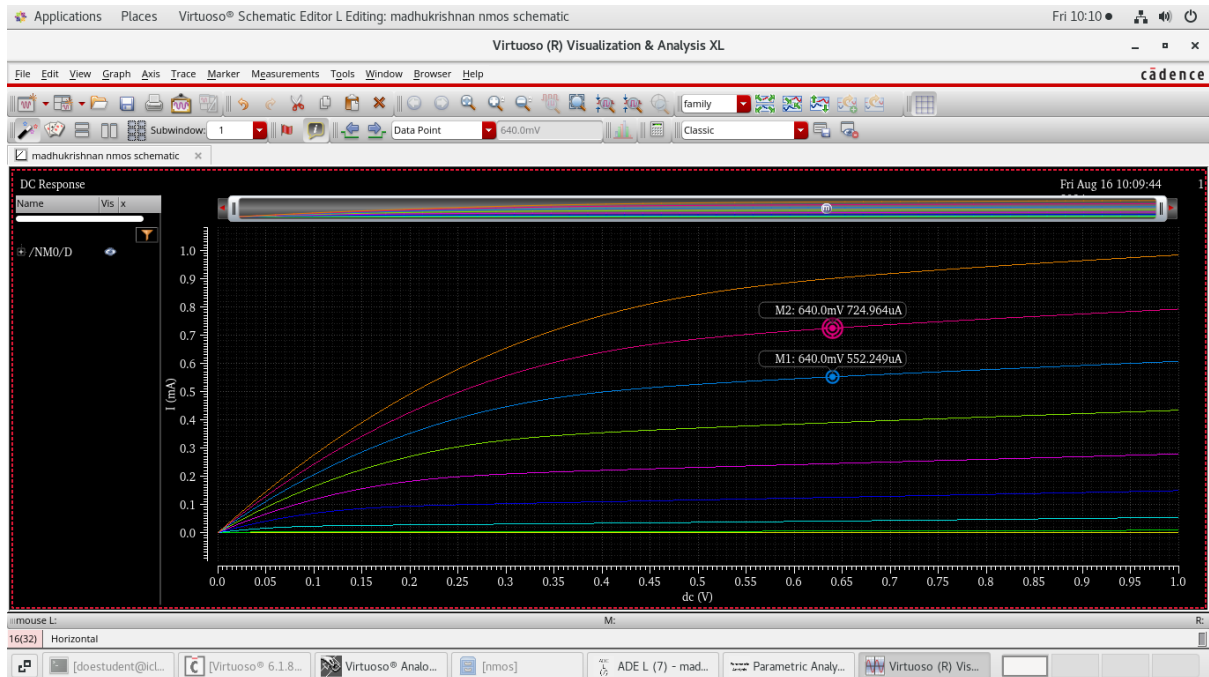


I_{DS} vs V_{DS} for $V_{GS} = 1V$

$$V_{T0} = 139 \text{ mV}$$

EXTRACTION OF PARAMETERS

Parametric analysis is done for varying V_{GS} to extract parameters. The graph is plotted.



Parametric analysis graph

The following equation is used to find $I_{D SAT}$ and $\mu_n C_{ox}$

$$I_{D SAT} = \mu_n C_{ox} (W/L) ([V_{GS} - V_T] V_{D SAT} - (V_{D SAT})^2/2) \quad [2]$$

2 Points M1 and M2 with different V_{GS} is taken

For M1

$$V_{GS} = 777.8 \text{ mV}$$

$$I_{D SAT} = 552.249 \text{ } \mu\text{A}$$

For M2

$$V_{GS} = 888.9 \text{ mV}$$

$$I_{D SAT} = 724.964 \text{ } \mu\text{A}$$

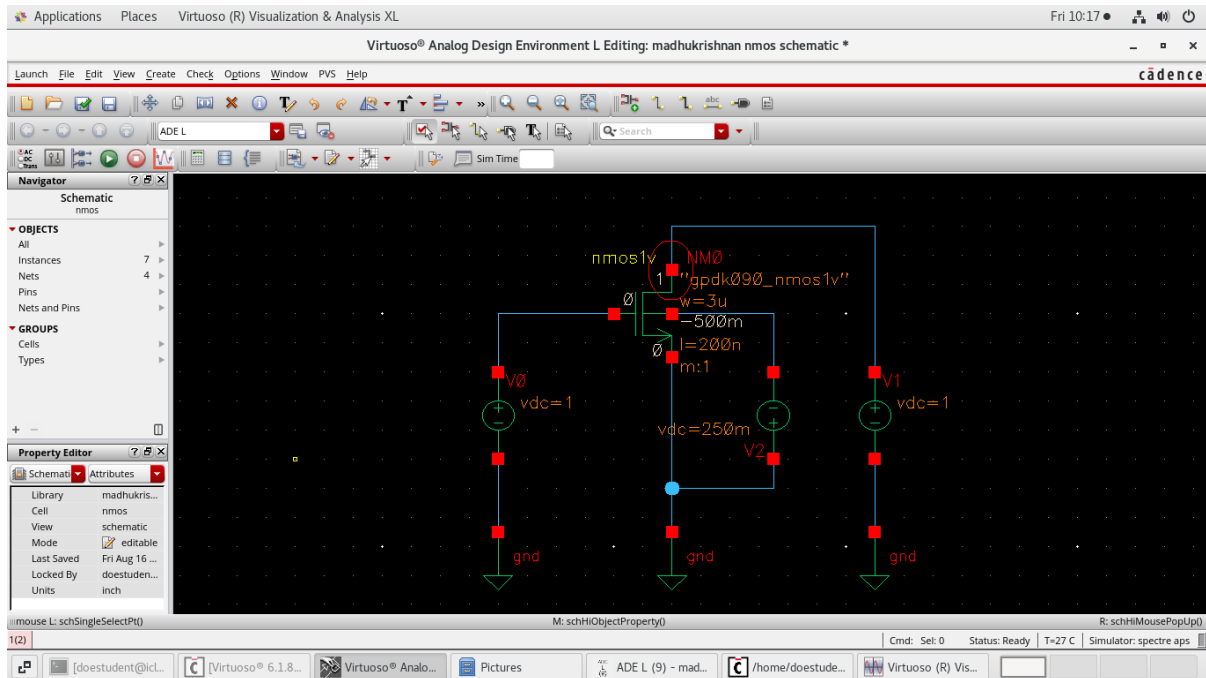
The above values are substituted in equation [2] and $V_{D SAT}$ is found. This is then substituted along with parameters of M1 to find $\mu_n C_{ox}$

$$V_{D SAT} = 0.56796 \text{ V}^{-1}$$

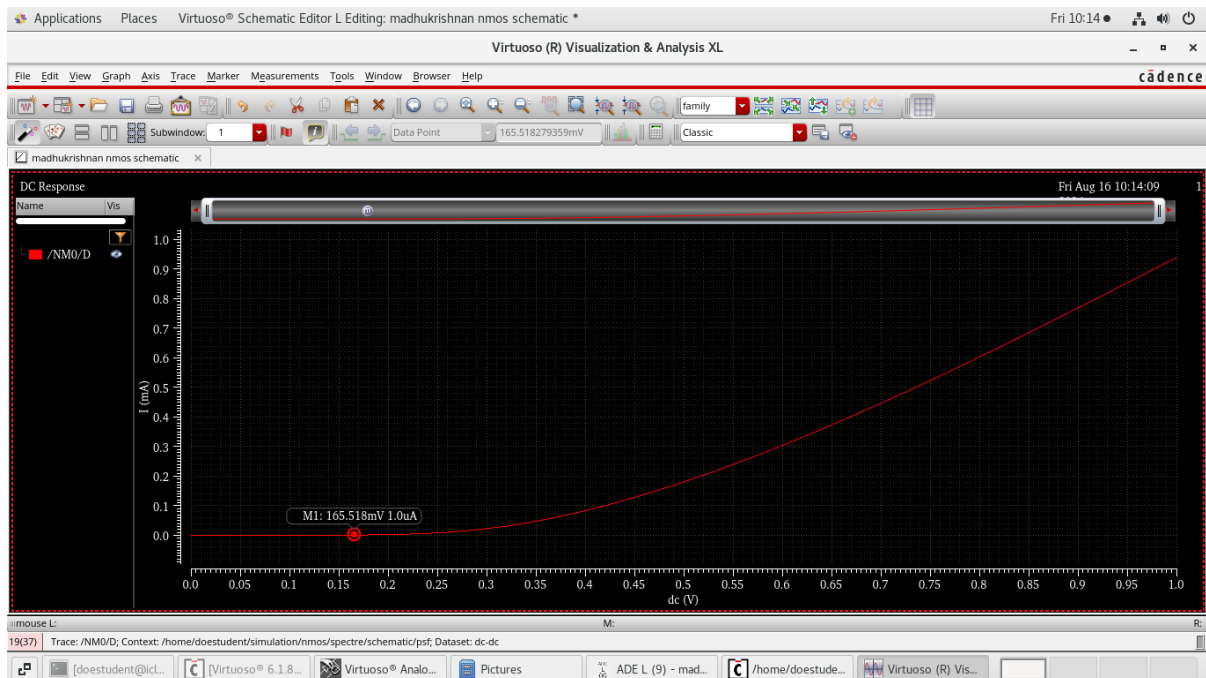
$$\mu_n C_{ox} = 182.691 \text{ } \mu\text{A/V}^2$$

V_{GS} is varied and V_T is noted using DC analysis of I_{DS} vs V_{DS} .

For $V_{GS} = 0.250\text{ V}$

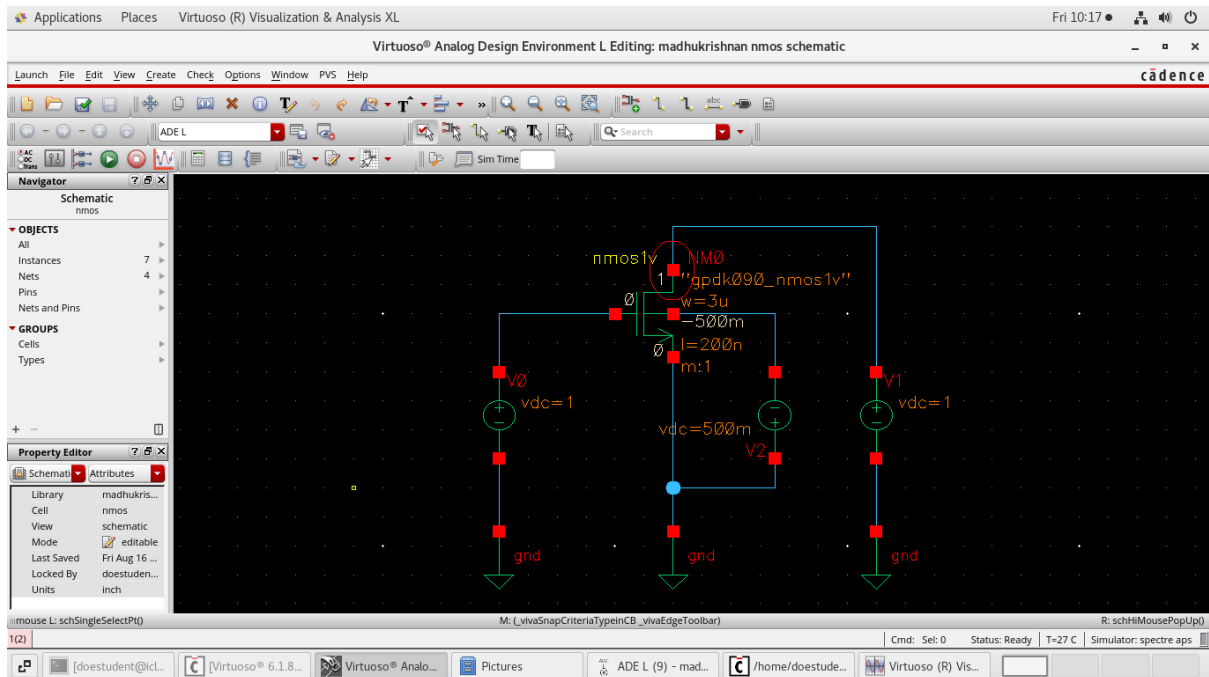


Schematic diagram

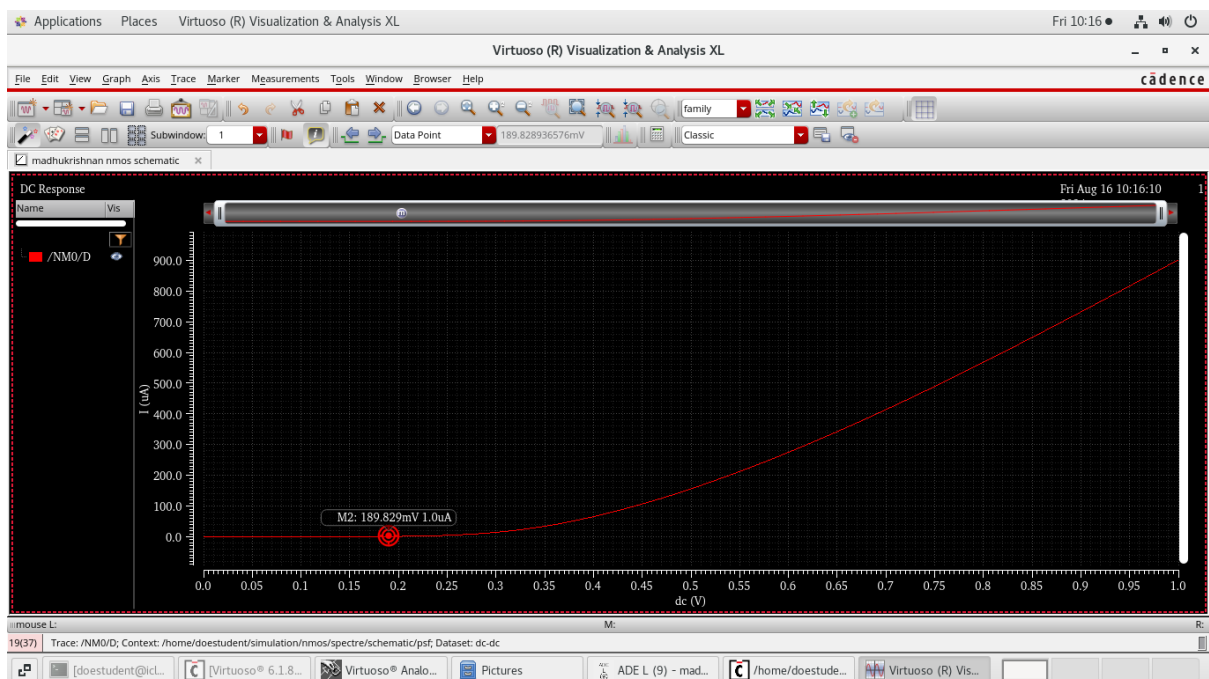


DC Analysis graph

For $V_{GS} = 0.500\text{ V}$

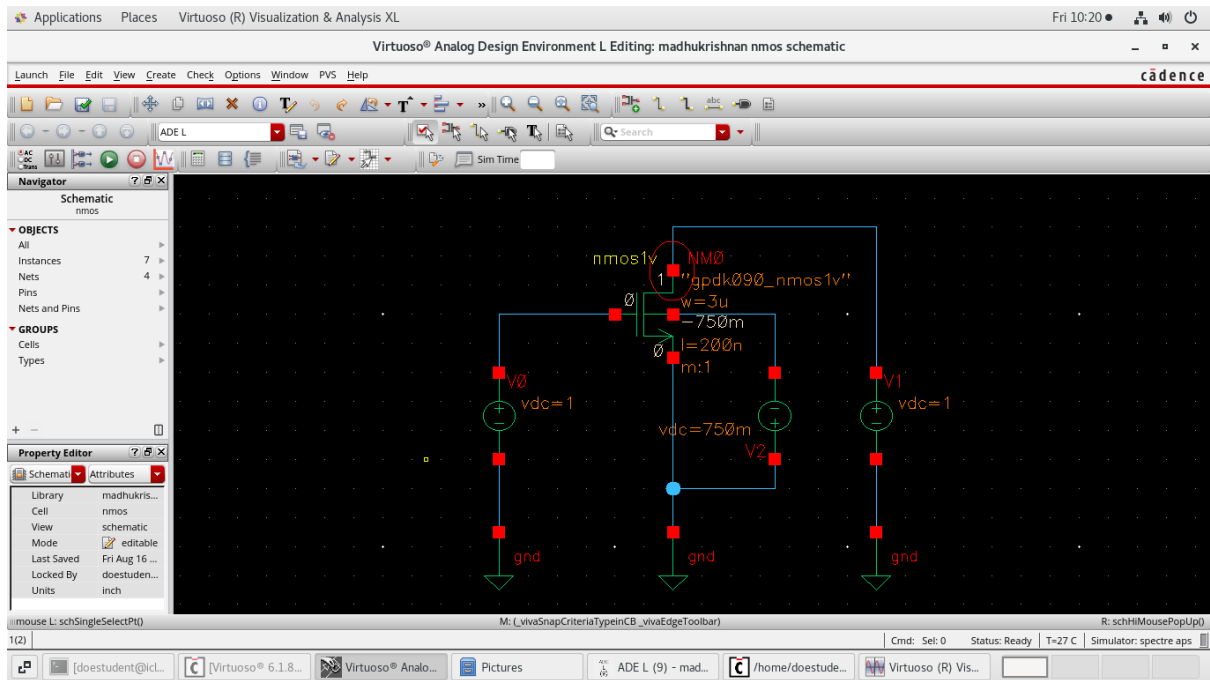


Schematic diagram

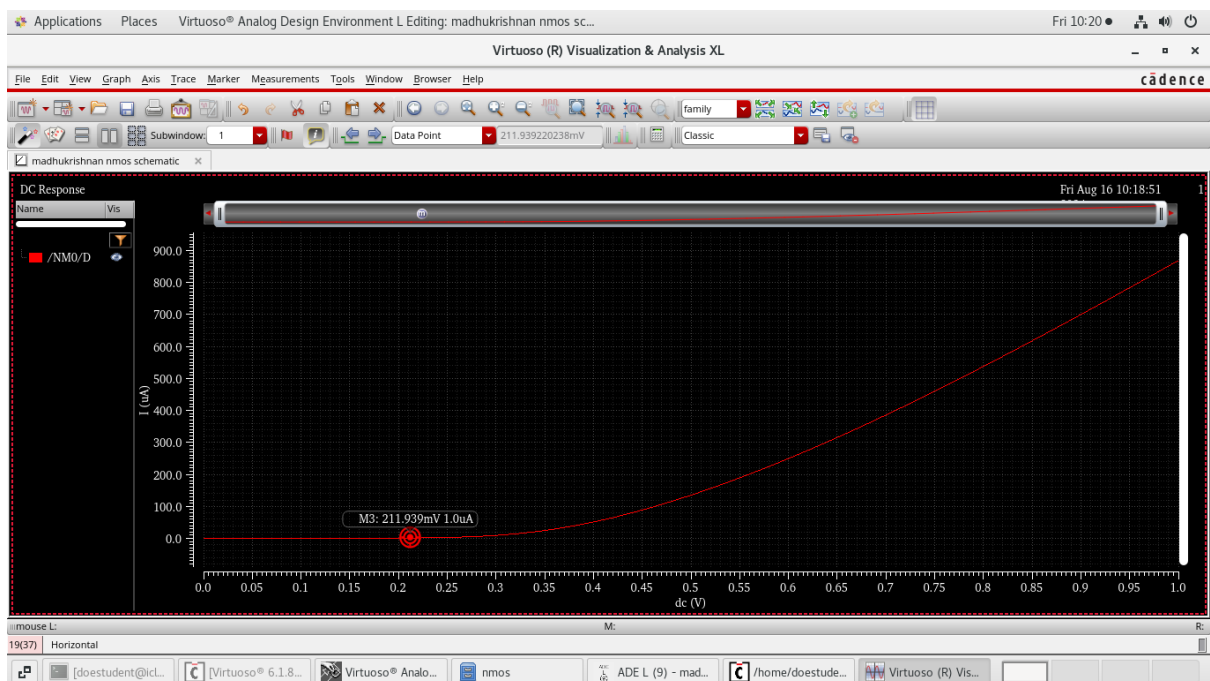


DC Analysis graph

For $V_{GS} = 0.750\text{ V}$



Schematic diagram



DC Analysis graph

The results are tabulated

V_{SB}	V_T
0 V	139 mV
250 mV	166 mV
500 mV	190 mV
750 mV	212 mV

A short channel n-MOSFET with following dimensions is placed in cellview.

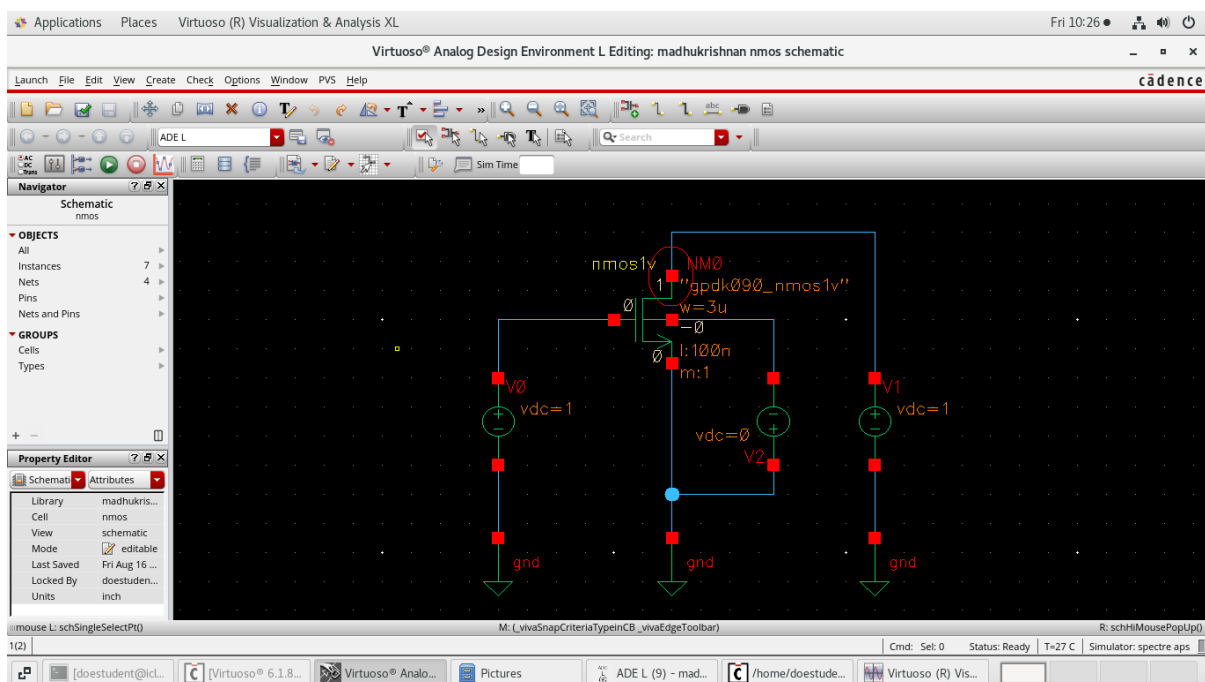
Length, 100 nm

Width, $W = 1 + (\text{Roll Number}/5) = 1 + (10/5) = 3\mu\text{m}$

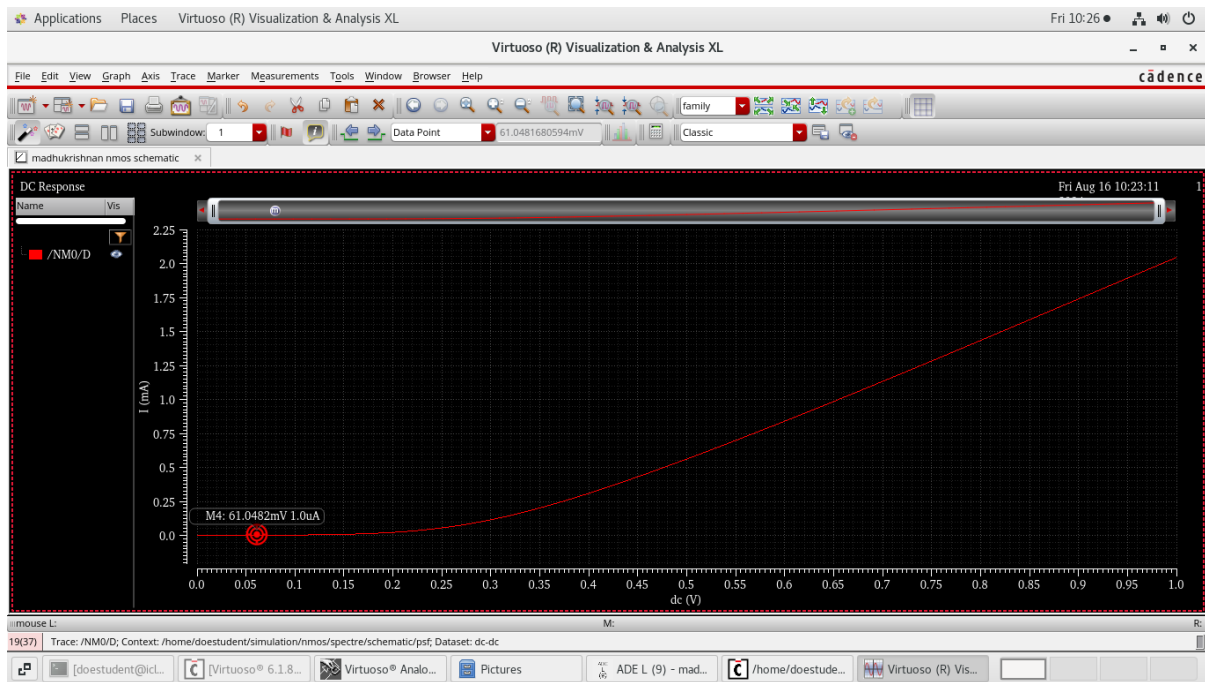
$W/L = 30$

$V_{DD} = 1\text{ V}$ is connected to the MOSFET.

$V_{SB} = 0\text{ V}$



Schematic diagram



I_{DS} vs V_{DS} for $V_{GS} = 1V$

$V_{T0} = 62 \text{ mV}$

EXTRACTION OF PARAMETERS

Parametric analysis is done for varying V_{GS} to extract parameters. The graph is plotted.



Parametric analysis graph

The following equation is used to find $I_{D\ SAT}$ and $\mu_n C_{ox}$

$$I_{D\ SAT} = \mu_n C_{ox} (W/L) ([V_{GS} - V_T] V_{D\ SAT} - (V_{D\ SAT})^2/2) \quad [3]$$

2 Points M1 and M2 with different V_{GS} is taken

For M1

$$V_{GS} = 777.8\text{ mV}$$

$$I_{D\ SAT} = 1.16296\text{ mA}$$

For M2

$$V_{GS} = 888.9\text{ mV}$$

$$I_{D\ SAT} = 1.49589\text{ mA}$$

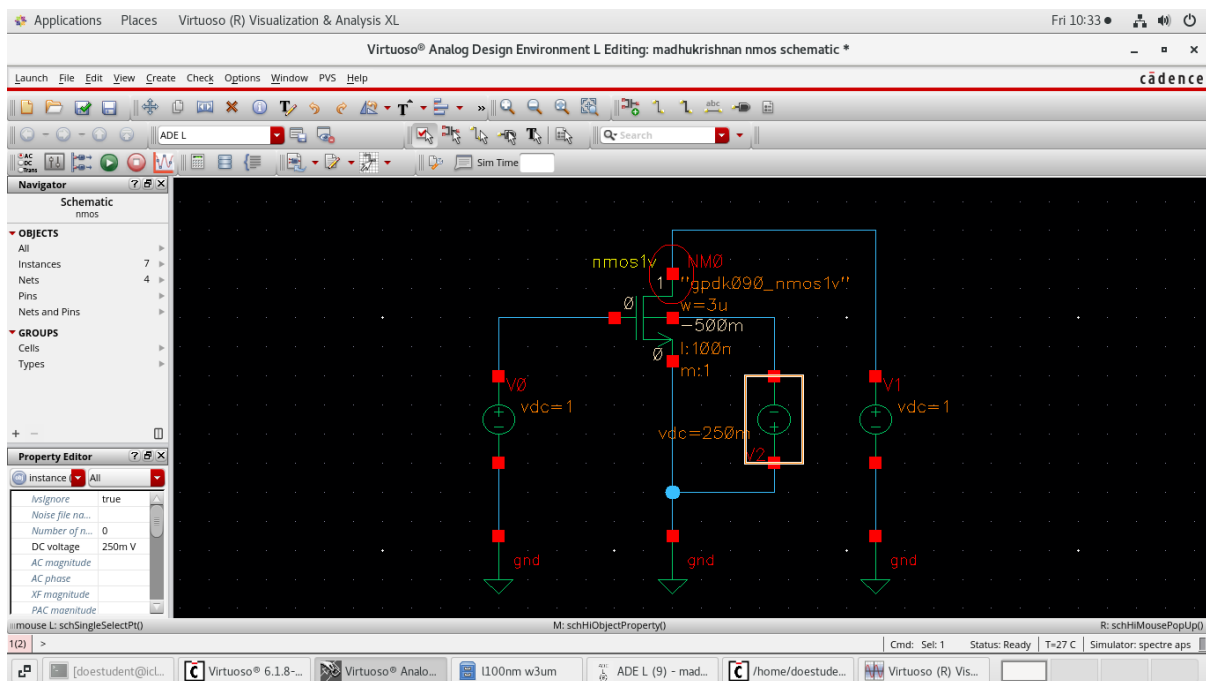
The above values are substituted in equation [3] and $V_{D\ SAT}$ is found. This is then substituted along with parameters of M1 to find $\mu_n C_{ox}$

$$V_{D\ SAT} = 0.60582\text{ V}$$

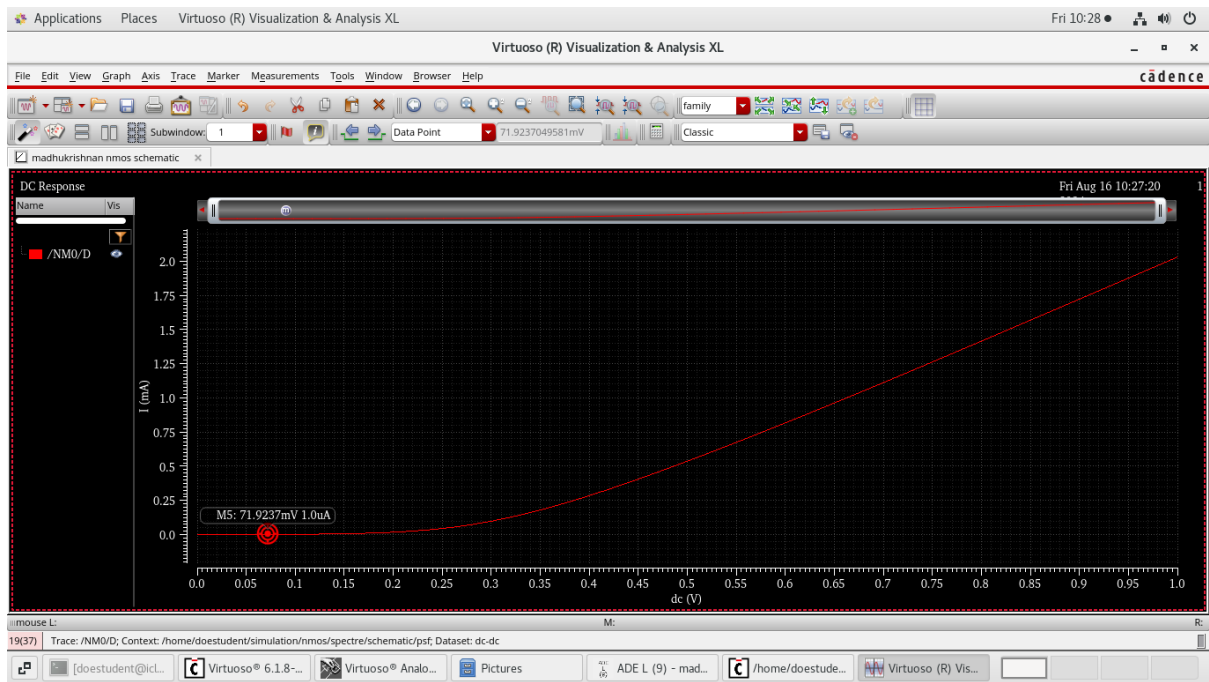
$$\mu_n C_{ox} = 154.976\text{ }\mu\text{A/V}^2$$

V_{GS} is varied and V_T is noted using DC analysis of I_{DS} vs V_{DS} .

For $V_{GS} = 0.250\text{ V}$

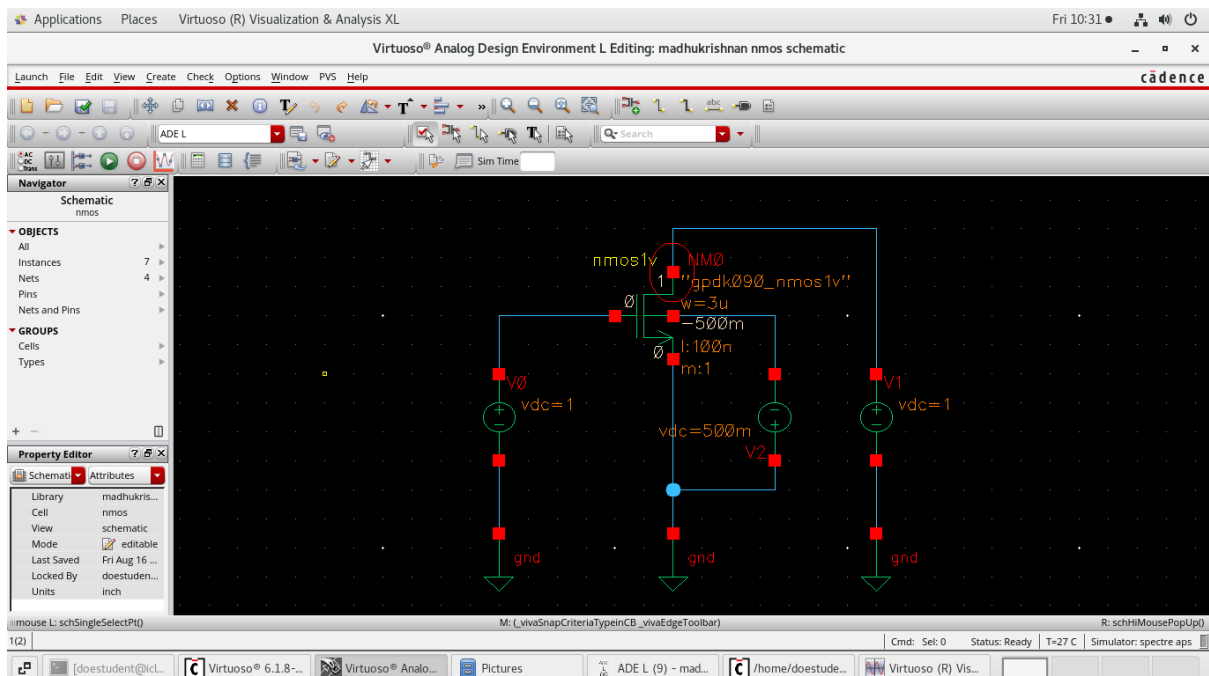


Schematic diagram

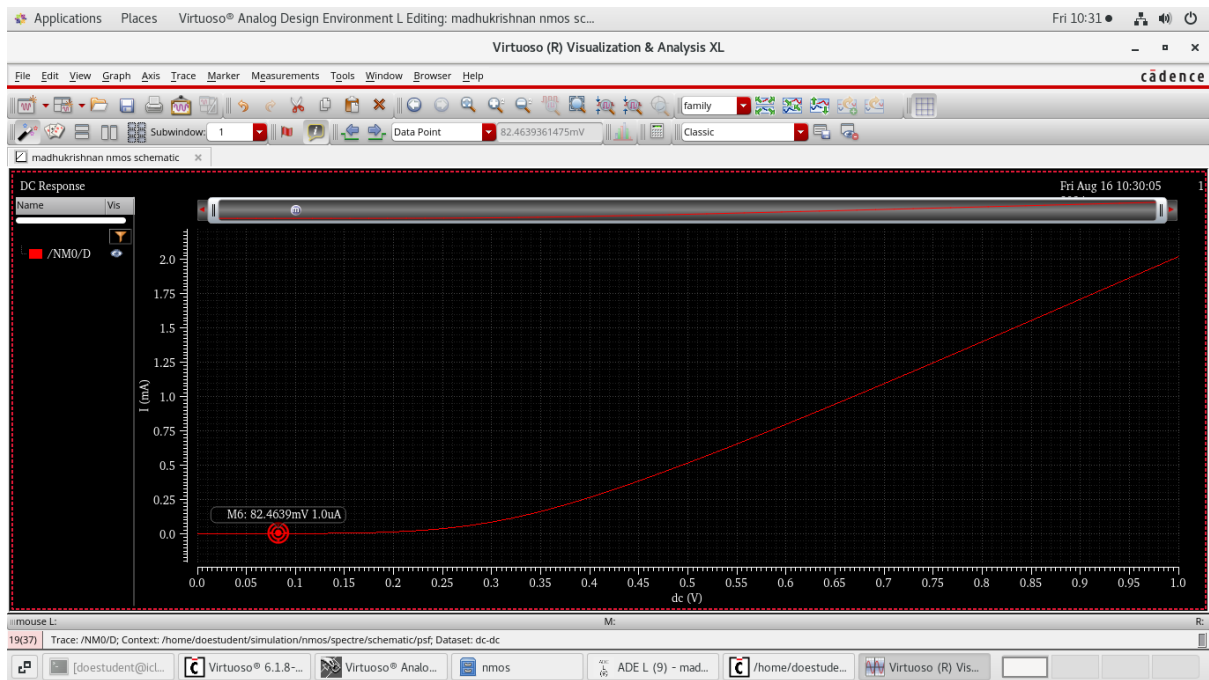


DC Analysis graph

For $V_{GS} = 0.500\text{ V}$

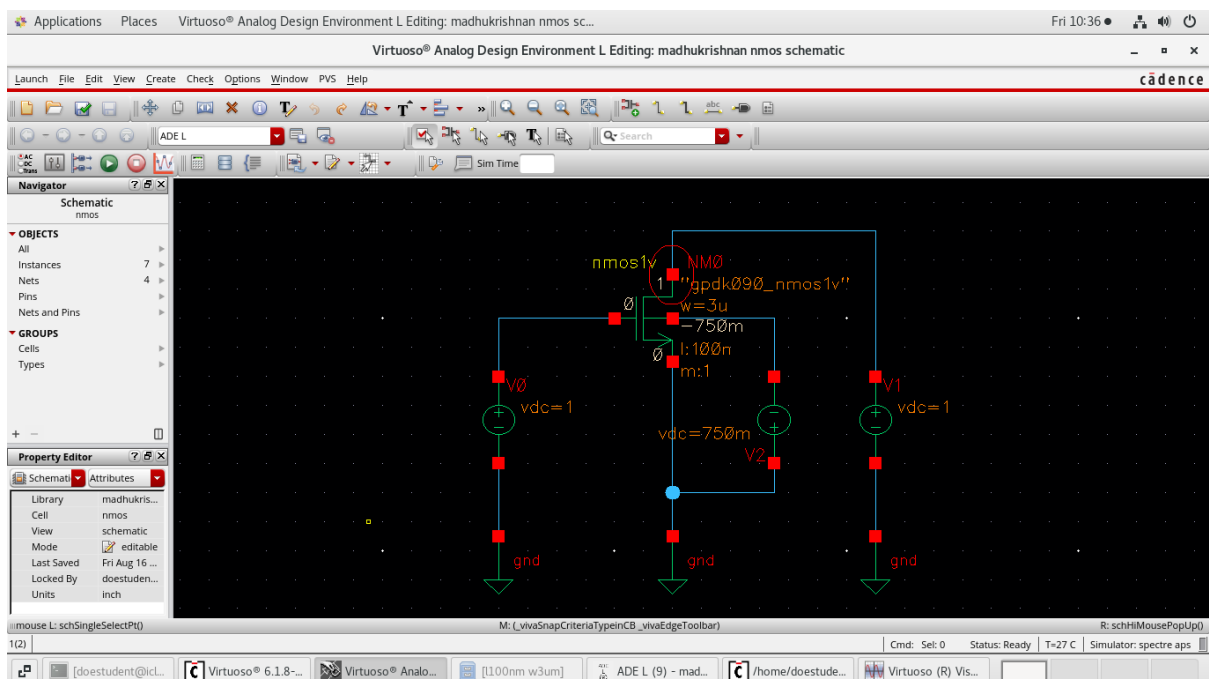


Schematic diagram

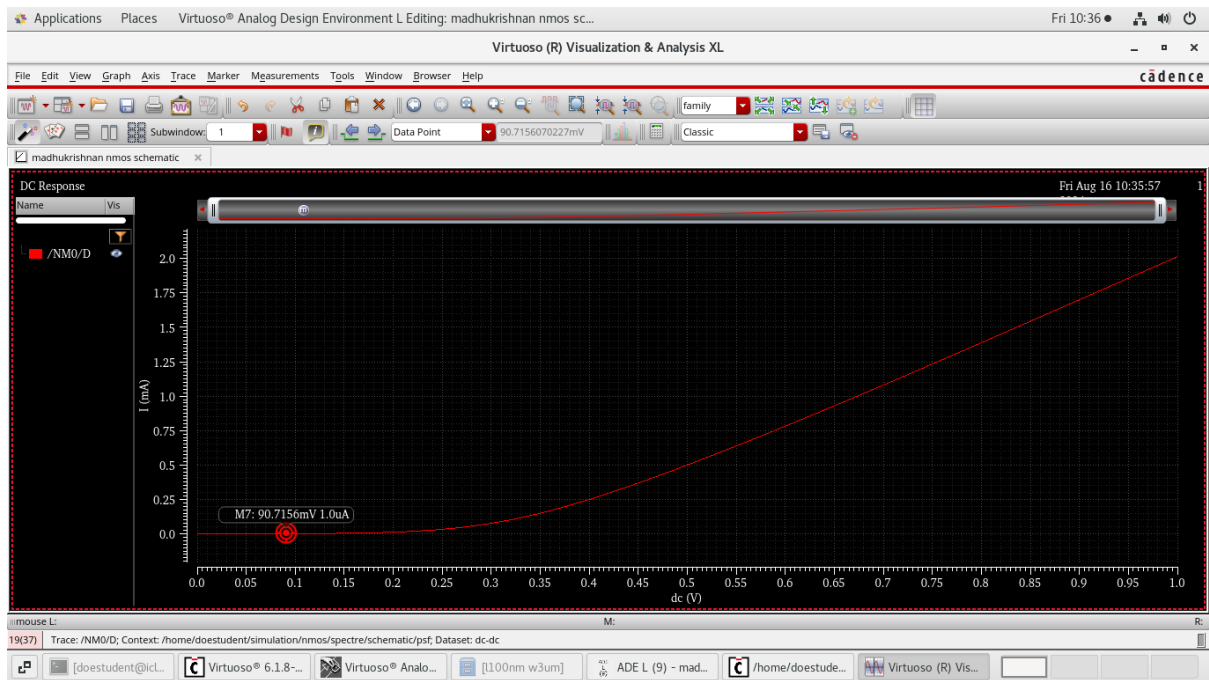


DC Analysis graph

For $V_{GS} = 0.750 \text{ V}$



Schematic diagram



DC Analysis graph

The results are tabulated

V_{SB}	V_T
0 V	62 mV
250 mV	72 mV
500 mV	85 mV
750 mV	91 mV

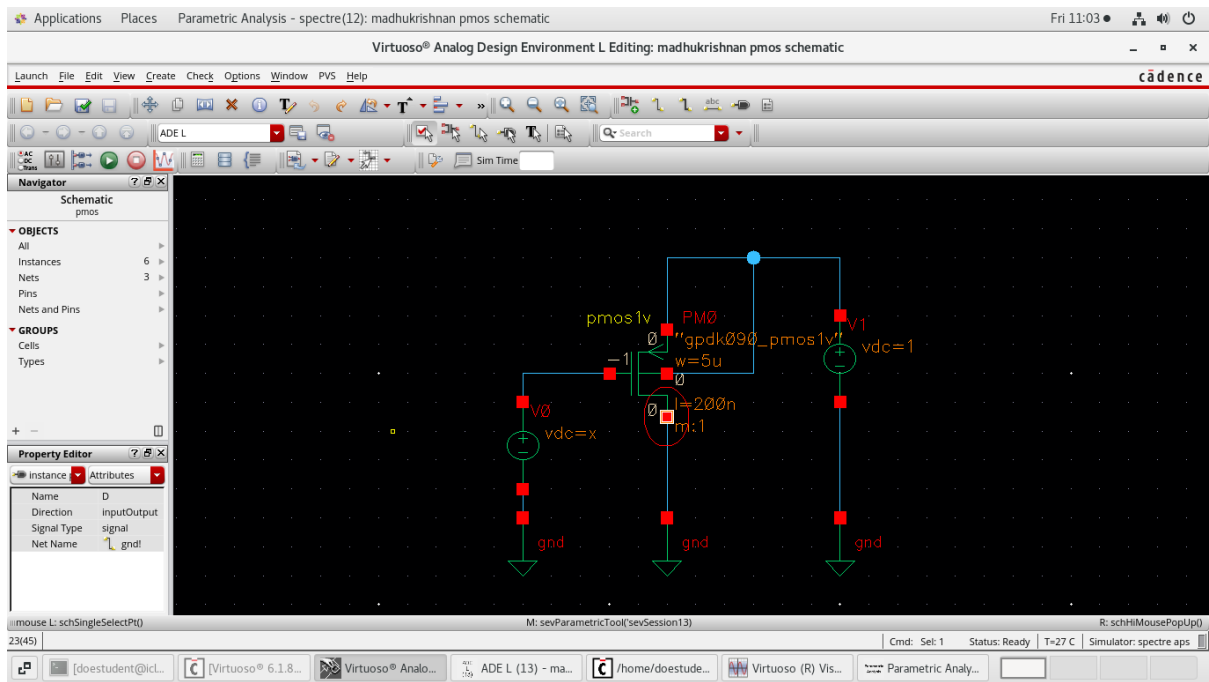
The threshold voltage is found to be reduced for equal V_{GS} and reduced length. The $V_{D SAT}$ is observed to be higher for 100nm MOSFET. The body effect can be seen in both 100nm and 200nm MOSFET.

p-MOSFET

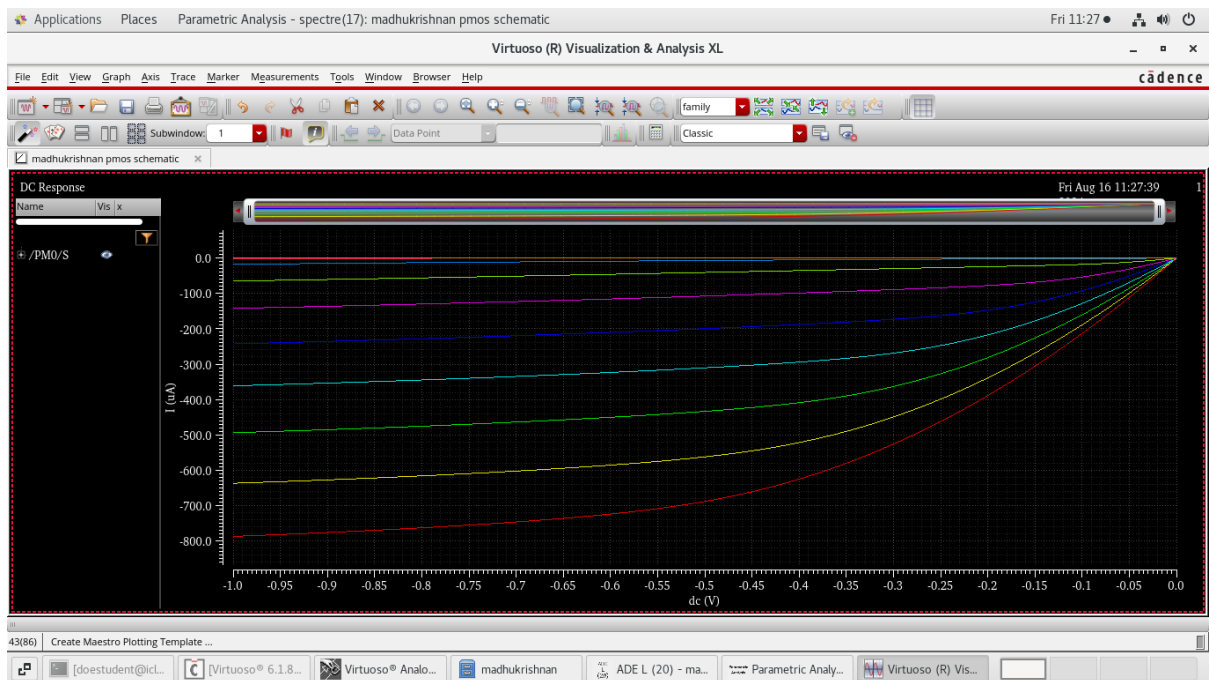
A p-MOSFET having following dimension is placed in cellview.

$L = 200 \text{ nm}$

$W = 3 \text{ } \mu\text{m}$



Schematic diagram



Parametric analysis graph

Parametric analysis is performed for V_{DS} vs I_{DS} with varying V_{GS}